What Is Claimed Is:

1. An exposure system, comprising:

a compensation unit to receive at least one adjustment value of a corresponding equipment parameter, and compensate a corresponding overlay parameter according to the adjustment value and an adjustment formula corresponding to the equipment parameter; and

an exposure device to perform overlay and exposure processes on a wafer using the compensated overlay parameter.

2. The exposure system as claimed in claim 1 wherein the compensation unit calculates a compensation value according to the adjustment value and the adjustment formula, and compensates the overlay parameter using the compensation value.

3. The exposure system as claimed in claim 2 wherein the equipment parameter is FIA_X, the affected overlay parameter is Offset_X, and the adjustment formula is,

B = (-1.0883*A)-0.0016,

wherein A is the adjustment value and B is the compensation value.

4. The exposure system as claimed in claim 2 wherein the equipment parameter is FIA_Y, the affected overlay parameter is Offset_Y, and the adjustment formula is,

B = (-1.0232*A)-0.0023,

wherein A is the adjustment value and B is the compensation value.

5. The exposure system as claimed in claim 2 wherein the equipment parameter is LSA_X, the affected overlay parameter is Offset_X, and the adjustment formula is

B = (-0.9958*A)+0.0011,

wherein A is the adjustment value and B is the compensation value.

6. The exposure system as claimed in claim 2 wherein the equipment parameter is LSA_Y, the affected overlay parameter is Offset_Y, and the adjustment formula is,

B = (-1.0042*A)-0.0004,

wherein A is the adjustment value and B is the compensation value.

7. The exposure system as claimed in claim 2 wherein the equipment parameter is Matching Offset X, the affected overlay parameter is Shot Scaling X, and the adjustment formula is,

B = (-84.853*A)+0.0639,

wherein A is the adjustment value and B is the compensation value.

8. The exposure system as claimed in claim 2 wherein the equipment parameter is Machine Scaling Y, the affected overlay parameter is Shot Scaling Y, and the adjustment formula is,

B = (-1.0053*A)-0.0193,

wherein A is the adjustment value and B is the compensation value.

9. The exposure system as claimed in claim 2 wherein the equipment parameter is Shot Skew, the affected overlay parameter is Shot Ortho, and the adjustment formula is,

B = (-0.9422*A)+0.0094,

wherein A is the adjustment value and B is the compensation value.

10. The exposure system as claimed in claim 2 wherein the equipment parameter is Machine Shot Rot, the affected overlay parameter is Shot Rot, and the adjustment formula is,

B = (-1.0247*A)-0.0214,

wherein A is the adjustment value and B is the compensation value.

11. An exposure method, comprising the steps of:

receiving at least one adjustment value of a corresponding equipment parameter;

compensating a corresponding overlay parameter according to the adjustment value and an adjustment formula corresponding to the equipment parameter; and

performing overlay and exposure processes on a wafer using the compensated overlay parameter.

12. The exposure method as claimed in claim 11 further comprising calculating a compensation value according to the adjustment value and the adjustment formula, and compensating the overlay parameter using the compensation value.

13. The exposure method as claimed in claim 12 wherein the equipment parameter is FIA_X, the affected overlay parameter is Offset_X, and the adjustment formula is,

B = (-1.0883*A)-0.0016,

wherein A is the adjustment value and B is the compensation value.

14. The exposure method as claimed in claim 12 wherein the equipment parameter is FIA_Y, the affected overlay parameter is Offset_Y, and the adjustment formula is,

B = (-1.0232*A)-0.0023,

wherein A is the adjustment value and B is the compensation value.

15. The exposure method as claimed in claim 12 wherein the equipment parameter is LSA_X, the affected overlay parameter is Offset_X, and the adjustment formula is,

B = (-0.9958*A)+0.0011,

wherein A is the adjustment value and B is the compensation value.

16. The exposure method as claimed in claim 12 wherein the equipment parameter is LSA_Y, the affected overlay parameter is Offset_Y, and the adjustment formula is,

B = (-1.0042*A)-0.0004,

wherein A is the adjustment value and B is the compensation value.

17. The exposure method as claimed in claim 12 wherein the equipment parameter is Matching Offset X, the affected overlay parameter is Shot Scaling X, and the adjustment formula is,

B = (-84.853*A)+0.0639,

wherein A is the adjustment value and B is the compensation value.

18. The exposure method as claimed in claim 12 wherein the equipment parameter is Machine Scaling Y, the affected overlay parameter is Shot Scaling Y, and the adjustment formula is,

B = (-1.0053*A)-0.0193,

wherein A is the adjustment value and B is the compensation value.

19. The exposure method as claimed in claim 12 wherein the equipment parameter is Shot Skew, the affected overlay parameter is Shot Ortho, and the adjustment formula is,

B = (-0.9422*A)+0.0094,

wherein A is the adjustment value and B is the compensation value.

20. The exposure method as claimed in claim 12 wherein the equipment parameter is Machine Shot Rot, the affected overlay parameter is Shot Rot, and the adjustment formula is,

B = (-1.0247*A)-0.0214,

wherein A is the adjustment value and B is the compensation value.